

Applic. No.: 10/680,379
Amdt. Dated October 15, 2007
Reply to Office action of July 26, 2007

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Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of claims:

Claim 1 (currently amended). A method for doping electrically conductive organic compounds, which comprises:

introducing a doping substance activated by exposure with an activation radiation into an electrically conductive organic compound;

irreversibly fixing the activatable doping substance in the organic compound in regions that adjoin a source contact and a drain contact as a result of exposing the organic compound with the activation radiation;

removing unbounded doping substance at reduced pressure or elevated temperature from the organic compound after the exposure; and

restoring original electrical conductivity in unexposed regions.

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Claim 2 (original). The method according to claim 1, which further comprises carrying out the irreversible fixing of the doping substance by at least one of forming a covalent bond and forming a coordinate bond to the organic compound.

Claim 3 (original). The method according to claim 1, which further comprises providing the organic compound as an organic semiconductor.

Claim 4 (original). The method according to claim 1, which further comprises carrying out the exposure of the organic compound section by section.

Claim 5 (original). The method according to claim 4, which further comprises carrying out the section by section exposure utilizing a photomask.

Claim 6 (original). The method according to claim 1, which further comprises:

providing light-opaque regions opaque to the activation radiation used for the exposure in the organic compound; and

during the exposure, obtaining unexposed sections in the organic compound, the unexposed sections being disposed behind

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the light-opaque regions as seen in a direction of a radiation source used for the exposure to the organic compound.

Claim 7 (original). The method according to claim 6, which further comprises forming the light-opaque regions by a gate electrode.

Claim 8 (original). The method according to claim 6, which further comprises forming the light-opaque regions utilizing a gate electrode.

Claim 9 (currently amended). A method for fabricating an organic field-effect transistor, which comprises:

depositing a gate electrode, a source contact, a drain contact, a gate dielectric, and an electrically conductive organic semiconductor arranged between the source contact and drain contact on a substrate;

introducing a doping substance activated by exposure with an activation radiation into the organic semiconductor;

carrying out section-by-section exposure with the activation radiation;

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after the exposure, removing unbounded doping substance at reduced pressure or elevated temperature from the organic semiconductor to irreversibly fix, in regions of the organic semiconductor adjoining the source contact and the drain contact, the doping substance in the organic semiconductor and to obtain contact regions adjoining the source contact and the drain contact, the contact regions having increased electrical conductivity, wherein a first distance is retained between the gate dielectric and the source contact and a second distance is retained between the gate dielectric and the drain contact, at which the organic semiconductor is applied directly with the contact region to the substrate; and

restoring original electrical conductivity in unexposed regions.

Claim 10 (original). The method according to claim 9, which further comprises applying a photomask for the section-by-section exposure.

Claim 11 (original). The method according to claim 9, which further comprises carrying out the section-by-section exposure by applying a photomask.

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Claim 12 (original). The method according to claim 9, which further comprises:

providing the substrate as a substrate transparent to the activation radiation;

carrying out the depositing step by depositing, on the substrate, the source and drain contacts spaced apart from the gate electrode;

depositing a gate dielectric on the gate electrode to obtain a spacing in which the substrate is uncovered between the gate dielectric and the source contact and also between the gate dielectric and the drain contact;

depositing the organic semiconductor on the substrate, the source contact, the drain contact, and the gate dielectric to fill, with the organic semiconductor, at least one of the spacing between the gate dielectric and the source contact and the spacing between the gate dielectric and the drain contact;

carrying out the exposure step with the activation radiation from a side of the substrate to obtain, adjoining the source contact and the drain contact, contact regions having increased conductivity in the organic semiconductor; and

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subsequently removing excess doping substance from the organic semiconductor.

Claim 13 (original). The method according to claim 9, which further comprises simultaneously depositing the gate electrode, the source contact, and the drain contact on the substrate.

Claim 14 (original). The method according to claim 9, which further comprises constructing the gate dielectric from a material transparent to the activation radiation.

Claim 15 (original). The method according to claim 9, which further comprises providing the gate dielectric with a material transparent to the activation radiation.